What is claimed is:

1. A reflection-type liquid crystal display panel having a back panel comprising a flat back substrate, an insulating layer formed on an inner surface of the back substrate, and reflective electrodes formed on the insulating layer;

wherein the insulating layer has a surface provided with minute irregularities, and

the electrodes are formed on the surface of the insulating layer in a shape conforming to the minute irregularities formed in the surface of the insulating layer .

2. The reflection-type liquid crystal display panel according to claim 1, wherein TFTs are formed on the back substrate(10a).

3. The reflection-type liquid crystal display panel according to claim 1, wherein the minute irregularities include ridges and valleys, and the height of the ridges of the minute irregularities is in the range of 0.4 to 10 μm.

4. The reflection-type liquid crystal display panel according to claim 1, wherein the electrodes are formed by patterning a metal thin film having a thickness of 1 μm or below.

5. A reflection-type liquid crystal display panel having a back panel comprising a flat back substrate, an insulating layer formed on an inner surface of the back substrate, and reflective electrodes formed on the insulating layer;

wherein the insulating layer is divided into portions arranged in a pattern which is substantially the same as a pattern in which the electrodes are

arranged.

6. The reflection-type liquid crystal display panel according to claim 5, wherein TFTs are formed on the back substrate.

7. The reflection-type liquid crystal display panel according to claim 5, wherein the insulating layer has a surface provided with minute irregularities, and the back electrodes are formed on the insulating layer in a shape conforming to the minute irregularities of the insulating layer.

8. The reflection-type liquid crystal display panel according to claim 5, wherein the minute irregularities include ridges and valleys, and the height of the ridges of the minute irregularities is in the range of 0.4 to 10 μm.

9. The reflection-type liquid crystal display panel according to claim 5, wherein the first electrodes are formed by patterning a metal thin film having a thickness of 1 μm or below.

10. A method of fabricating a reflection-type liquid crystal display panel having a back panel comprising a flat back substrate, an insulating layer formed on an inner surface of the back substrate, and reflective electrodes formed on the insulating layer; said method comprising the steps of:

forming an insulating photosensitive resin layer on an inner surface of the back substrate;

exposing the photosensitive resin layer to light through a transparent sheet having a surface provided with minute irregularities after drying the photosensitive resin layer;

subjecting the exposed photosensitive resin layer

to a developing process and drying the developed photosensitive resin layer to form an insulating layer having a surface provided with minute irregularities; and

forming a reflective metal film on the surface of the insulating layer provided with the minute irregularities .

11. A method according to claim 10, wherein the transparent sheet having the surface provided with the minute irregularities is a ground glass plate.

12. A method according to claim 10, wherein the minute irregularities is in the range of 0.4 to 10 μm.

13. A method of fabricating a reflection-type liquid crystal display panel having a back panel comprising a flat back substrate, TFTs formed on an inner surface of the back substrate, an insulating layer formed on the inner surface of the back substrate, and reflective electrodes formed on the insulating layer; said method comprising the steps of:

forming an insulating photosensitive resin layer on an inner surface of the back substrate and drying the same;

exposing the photosensitive resin layer to light through a transparent sheet having a surface provided with minute irregularities after drying the photosensitive resin layer;

exposing the photosensitive resin layer to light through a photomask provided with a contact hole pattern for forming contact holes;

subjecting the exposed photosensitive resin layer to a developing process and drying the developed photosensitive resin layer to form an insulating layer having a surface provided with minute irregularities

(12m); and

forming a reflective metal film on the surface of the insulating layer provided with the minute irregularities .

14. A method according to claim 13, wherein the transparent sheet having the surface provided with the minute irregularities is a ground glass plate.

15. A method according to claim 13, wherein the minute irregularities include ridges and valleys, and the height of the ridges of the minute irregularities is in the range of 0.4 to 10 μm.

16. A method of fabricating a reflection-type liquid crystal display panel having a back panel comprising a flat back substrate, an insulating layer formed on an inner surface of the back substrate (10a), and reflective electrodes formed on the insulating layer; said method comprising the steps of:

forming an insulating photosensitive resin layer on an inner surface of the back substrate and drying the same;

exposing the photosensitive resin layer to light through a photomask provided with a pattern which is substantially the same as a pattern in which the electrodes are arranged after drying the photosensitive resin layer;

subjecting the exposed photosensitive resin layer to a developing process and drying the developed photosensitive resin layer to form an insulating layer;

forming a reflective metal film on the surface of the insulating layer; and

patterning the reflective metal film to form the first electrodes.

17. The method according to claim 16, further

comprising the step of exposing the photosensitive resin layer to light through a transparent sheet having a surface provided with minute irregularities subsequent to the step of forming the insulating photosensitive resin layer on the inner surface of the back substrate and drying the same, whereby minute irregularities are formed in a surface of the photosensitive resin layer after the photosensitive resin layer is processed by a developing process and dried.

18. The method according to claim 17, wherein the transparent sheet is a ground glass plate.

19. The method according to claim 17, wherein the minute irregularities formed in the surface of the photosensitive resin layer include ridges and valleys, and the height of the ridges of the minute irregularities is in the range of 0.4 to 10 μm.

20. A method of fabricating a reflection-type liquid crystal display panel having a back panel comprising a flat back substrate, TFTs formed on an inner surface of the back substrate, an insulating layer formed on the inner surface of the back substrate, and reflective electrodes formed on the insulating layer in a predetermined pattern; said method comprising the steps of:

forming an insulating photosensitive resin layer on an inner surface of the back substrate and drying the same;

exposing the photosensitive resin layer to light through a photomask provided with a pattern which is substantially the same as the pattern of the first electrodes and including a pattern of contact holes;

subjecting the exposed photosensitive resin layer to a developing process and drying the developed photosensitive resin layer to form the insulating layer;

and

forming a reflective metal film on the surface of the insulating layer; and

patterning the reflective metal film in the pattern of the electrodes.